

IN THE SPECIFICATION

Please insert the following new heading and paragraph at page 1, line 6:

**CROSS REFERENCES TO RELATED APPLICATIONS**

This application is a national stage application of International Patent Application No. PCT/JP03/05442, filed on April 28, 2003, and claims priority to Japanese Patent Application No. 2002-136183, filed on May 10, 2002, both of which are incorporated herein by reference in their entireties.

Please replace the Abstract at page 19 with the following rewritten Abstract:

**ABSTRACT OF THE DISCLOSURE**

Provided are a novel halogenoacetoxyadamantane derivative which is useful as a modifying agent for a resin for a photoresist and a dry etching resistance-improving agent in the photolithography field, agricultural and medical intermediates and a compound for other various industrial products and a process for producing the same. To be specific, provided are a halogenoacetoxyadamantane derivative having a halogenoacetoxy group in an adamantane skeleton and a process for producing a halogenoacetoxyadamantane derivative, comprising the step of reacting a hydroxyl group of an adamantane skeleton with halogenoacetic halide or reacting the above hydroxyl group with a lithiation agent to derive it into a lithiumoxy group and then reacting halogenoacetic halide to introduce a halogenoacetoxy group.